METHOD FOR REDUCING MASK PRECIPITATION DEFECTS

ABSTRACT OF THE DISCLOSURE

In a container for transporting a reticle during a semiconductor manufacturing process, the reticle including a base made of isolating material and a metallic layer deposited onto a surface of the base, disclosed is a method for isolating and removing environmental contaminants which includes filling the container with inert gas, thereby purging the environmental contaminants, as well as inlet and outlet features to allow for the purging of clean inert gas and impurities.

Figure 1